

4

x

: 1

: 2

: 3

: 12, 22

: 13

: 23

가 ,

가

가

(vertically aligned mode)가 가

가
가

(retardation)
가

가
가

1 (polarizer) 2

(analyzer)가

1 2

가

가

가 가

1, 1, 2, 1, 2, C, C, R₀ < 10

TAC R_{th} 45nm TAC 65nm
C R₀ R_{th}

$$R_{0(C)} = [0.0028 \times (R_{th(C)})^2 - 0.00833 \times R_{th(C)} + 50] \pm 15nm$$

$$R_{th(C)} = [-0.0007 \times (R_{th(C)})^2 - 0.9583 \times R_{th(C)} + 165] \pm 20nm$$

C TAC
C R_{th}=50nm TAC 1 R₀ R_{th} 43 R₀ TAC 73, 95 R_{th} 13
5, TAC 2 R₀ R_{th} 135

C R_{th}=60nm TAC 1 R₀ R_{th} 50 R₀ TAC 80, 85 R_{th} 125
TAC 2 R₀ R_{th} 35
R₀ 65, 85 R_{th} 125

C R_{th}=50nm TAC 2 R₀ R_{th} 65 R₀ TAC 95, 42 R_{th} 82
TAC 2 R₀ R_{th} 82
R₀ R_{th} 45 R₀ 75, 42 R_{th} 82, TAC 2 R₀ R_{th} 55 R₀ 85, 42 R_{th} 82

C R_{th}=60nm TAC 2 R₀ R_{th} 80 R₀ TAC 110, 20 R_{th}
60, TAC 2 R₀ R_{th} 60, TAC 2 R₀ R_{th} 65 R₀ 95, 20 R_{th} 60
2

1 가 가 가

1 1

2 (1, 2) (12, 22) (24) (1) 4 TAC (13, 15, 23, 25), C (3), 1 2 (1) (12, 22), 1 (2), (14)

(1) , , , 가 (2) (1) (1) (2)

(3) (1, 2) DBEF-D (12) Bepol Nipo (12, 22) , C (14) TAC , 1 2 C (14) TAC TAC 가 z - (n_x + n_y)/2] x d C n_x = n_y > n_z (14) R₀ = 0 R₀ = (n_x - n_y) x d, R_{th} = [n_z R₀ < 10 << R_{th} (14) TAC R₀ < 10 , 5R₀ < R_{th} (14) R₀ < 10 , 5R₀ < R_{th} (14) R_{th} R₀ C x, y, z (14) R_{th} n_x n_y n_z (24) (24) R_{th} R₀ C

[1] R₀() = [0.0028 x (R_{th}(C))² - 0.00833 x R_{th}(C) + 50] ± 15nm

[2] R_{th}() = [-0.0007 x (R_{th}(C))² - 0.9583 x R_{th}(C) + 165] ± 20nm

1 2 45° 85° 가 (24)

2 C (14) R_{th} x (24) R₀ R_{th} y

24) C (2) (14) (1) (

(24) 1 2 가 C (14)

[1]

		1	2	3	4
C	R _{th}	50	60	100	120
	R ₀	50	60	70	80
	R _{th}	115	105	62	40

C R_{th} 50, 60, 100, 120 TAC R_{th}가 50nm TAC R_{th}가 60nm TAC
 100μm 가 100nm 120nm R_{th}가 45nm 55nm TAC R_{th}가 55nm 65nm TAC R₀ 0 TAC 0~10nm (slow)
 axis) , TAC 1 C R₀ , R₀ TAC R₀
 , TAC 2 TAC R₀

[2]

		TAC //			
		50nm TAC 1	60nm TAC 1	50nm TAC 2	60nm TAC 2
C	R _{th}	50	60	100	120
	R ₀	58	65	80	95
	R _{th}	115	105	62	40

TAC 가 , TAC
 (lamination) TAC
 , TAC
 , TAC 1 3 R₀ TAC R₀

[3]

		TAC	
		50nm TAC 1	60nm TAC 1
C	R _{th}	50	60
	R ₀	50	50
	R _{th}	115	105

60nm TAC 1 (R₀=50, R_{th}=105) (Arton) (R₀=50, R_{th}=90) S-cina

, TAC 2 4 .

[4]

		50nm TAC 1	60nm TAC 1	50nm TAC 2	60nm TAC 2
		//TAC1 TAC2	//TAC1 TAC2	TAC1//TAC2	TAC1//TAC2
C R _{th}		100	120	100	120
	R ₀	70	80	60	70
	R _{th}	62	40	62	40

1 4 5 .

[5]

	TAC				
	TAC		R ₀	R _{th}	
1	50nm TAC 1	//TAC	58 ± 15	115 ± 20	Arton, S-cina, RAC
2		TAC	50 ± 15	115 ± 20	
3	60nm TAC 1	//TAC	65 ± 15	105 ± 20	
4		TAC	50 ± 15	105 ± 20	
5	50nm TAC 2	//TAC1//TAC2	80 ± 15	62 ± 20	
6		TAC1//TAC2	60 ± 15	62 ± 20	
7		//TAC1 TAC2	70 ± 15	62 ± 20	
8	60nm TAC 2	//TAC1//TAC2	95 ± 15	40 ± 20	
9		TAC1//TAC2	70 ± 15	40 ± 20	
10		//TAC1 TAC2	80 ± 15	40 ± 20	

C 1 10 TAC (14) TAC (12, 22) TAC (12, 22) TAC
 TAC R_{th}=45~65nm (retardation) 가 , R₀ 0~10nm 가
 TAC TAC
 10가 TAC 1 1 4 가 가 , 3 4
 2 2 3 4
 3 4

3 (2)
 3 , 4 (C/R)가 2 0
 80 , 3 가
 80 10
 4 (2)
 x
 4 , 3 4 2 x 가
 3 4가 2 가
 가 C 가 2 TAC
 2
 가 30000~40000 /m² , 10000~23000 /m² . 2

가 C (TAC)

(57)

1. 1
 1 ,
 1 2 ,
 1 2 ,
 1 ,
 1 ,
 2 C ,
 C 2
 , C R₀ < 10

2. 1
 1 ,
 1 2 TAC

2 3.

1 2 TAC R_{th} 45nm 65nm .

1 4.

C R₀ R_{th}

$$R_{0(C)} = [0.0028 \times (R_{th(C)})^2 - 0.00833 \times R_{th(C)} + 50] \pm 15nm$$

$$R_{th(C)} = [-0.0007 \times (R_{th(C)})^2 - 0.9583 \times R_{th(C)} + 165] \pm 20nm$$

1 5.

C TAC .

5 6.

C 45nm R_{th} 55nm TAC 1 R₀ R_{th} 43 R₀ , TAC 73, 95 R_{th}
135 2 .

5 7.

C 45nm R_{th} 55nm TAC 1 R₀ R_{th} 35 R₀ , TAC 65, 95 R_{th}
135 2 .

5 8.

C 55nm R_{th} 65nm TAC 1 R₀ R_{th} 50 R₀ , TAC 80, 85 R_{th}
125 2 .

5 9.

C 55nm R_{th} 65nm TAC 1 R₀ R_{th} 35 R₀ , TAC 65, 85 R_{th}
125 2 .

5 10.

C 45nm R_{th} 55nm TAC 2 R₀ R_{th} , 65 R₀ , TAC 95, 42
R_{th} 82 2 .

5 11.

C 45nm R_{th} 55nm TAC 2
 75, 42 R_{th} 82 . , TAC
 R₀ R_{th} 45 R₀

12.
 5 ,

C 45nm R_{th} 55nm TAC 2
 55 R₀ 85, 42 R_{th} 82 . , TAC
 R₀ R_{th}

13.
 5 ,

C 55nm R_{th} 65nm TAC 2
 R_{th} 60 2 . R₀ R_{th} , 80 R₀ 110, 20
 TAC

14.
 5 ,

C 55nm R_{th} 65nm TAC 2
 85, 20 R_{th} 60 . , TAC
 R₀ R_{th} 55 R₀

15.
 5 ,

C 55nm R_{th} 65nm TAC 2
 65 R₀ 95, 20 R_{th} 60 . , TAC
 R₀ R_{th}

16.
 1 ,

1

17.
 1 ,

1

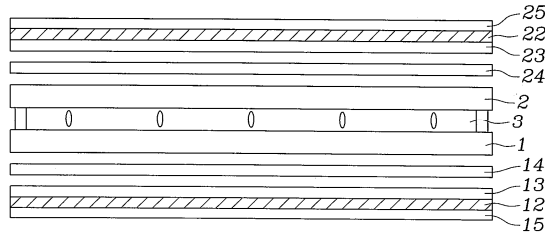
, 2

18.
 1 ,

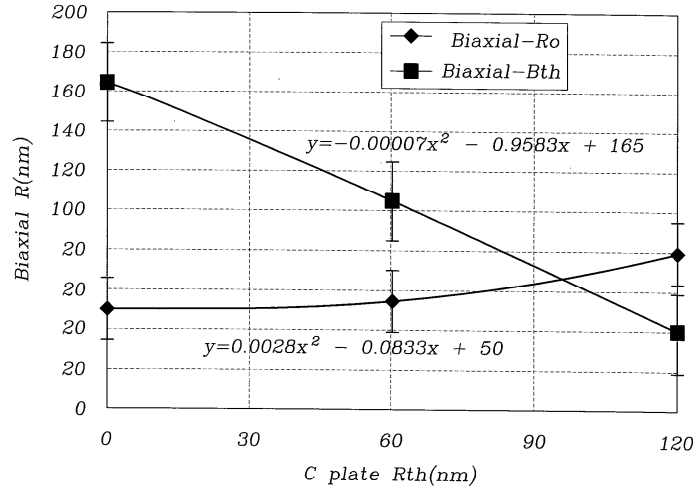
1

, 2

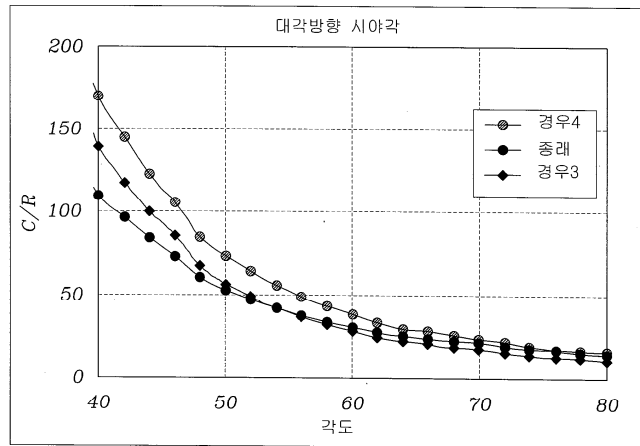
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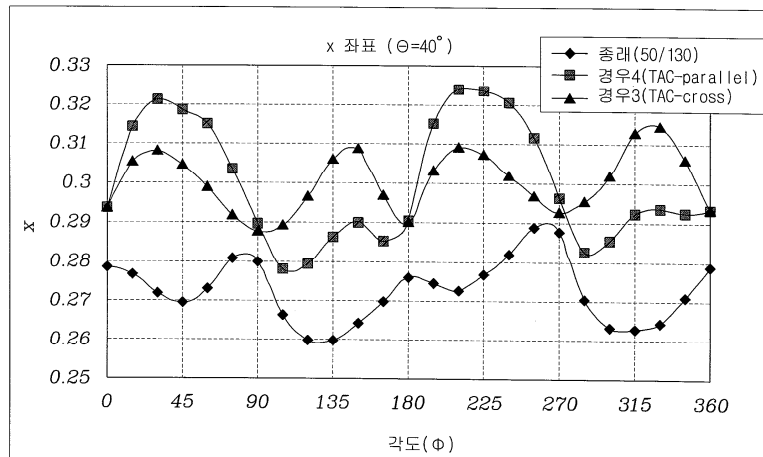
2



3



4



专利名称(译)	液晶显示器		
公开(公告)号	KR1020040056969A	公开(公告)日	2004-07-01
申请号	KR1020020083710	申请日	2002-12-24
[标]申请(专利权)人(译)	三星电子株式会社		
申请(专利权)人(译)	三星电子有限公司		
当前申请(专利权)人(译)	三星电子有限公司		
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IPC分类号	G02F1/1335 G02B5/30 G02F1/13363		
CPC分类号	G02F1/133634		
其他公开文献	KR100910559B1		
外部链接	Espacenet		

摘要(译)

用于包括薄膜晶体管基板的液晶显示器，面向薄膜晶体管基板的滤色器阵列面板，注入在这些双板之间的液晶层，设置在滤色器阵列面板外部的双轴补偿膜，第一偏振片设置在双轴补偿膜的外侧，C板一轴补偿膜设置在薄膜晶体管基板的外侧，并且第二偏振片设置在一个轴补偿膜的外侧。液晶显示器，双轴补偿膜和C板单轴补偿膜。

